Tool ID: 318 Tool Location: 110

Equipment Information Sheet

AJA Sputter Deposition - 3

Manager:Tom Pennell607-254-4309Calls to staff phones will be automatically forwarded to their cell phones duringBackup:Mac McMurdy607-254-4813Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.

<u>SAFETY</u>

USAGE RESTRICTIONS

• Users must remain in the cleanroom near the tool when the power supplies are in operation

SCHEDULING/SIGN-UP RESTRICTIONS

• Maximum 4 hour block reservations any time

- Must leave a 4 hour block between reservations
- Maximum of 12 hours reserved in advance at any time

MATERIALS COMPATIBILITY CATEGORY

Tool Category 4: Glass and Metal Categories	
Allowed	Not Allowed
Tool category 1/1E, 2, and 3 materials	
Silicon Based Substrates and Films	No CNF Class A metals
III/V compound Semiconductors	No Exposed CNF Group B metals- metals can be buried/covered with staff approval
Glass Substrates	Cannot be used as an etch stop
PECVD and ALD Films	
Buried Class B Metals with approval	
Organic/Bio Materials prepped w/o Salt Buffers	
Cured organics and baked Photoresist	No High Vapor pressure materials

High Vapor Pressure Metals and Compounds are materials that have a vapor pressure above 1e-6 Torr at 400 C.

Additional Material Restrictions and Exceptions

• Tool users should discuss their specific materials needs with staff

Last Updated: 03/16/2022

Minimum Tool Time: 15

minutes